

Entegris EUV pod status and update

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Agenda

- Current Status of EUV pod
 - Manufacturing
 - Delivery
 - Field Installation
 - Reports from the field
- Other
 - Shipping status
 - Continued investment into EUV
 - Facilities
 - Metrology
- Summary

Current Status of EUV pod

■ Manufacturing

- Product remains in pilot production
 - Plans on schedule for RTM by Q4-12
- Final clean on schedule for Q4 installation
- Transfer to Advanced Technology Manufacturing Center to take place late 2012

■ Delivery

- Process capabilities defined
 - Yields improving
 - Vendor capacity constraints currently resulting in product allocation across all customers
 - Constraints targeted for improvement by January 2012
- ## ■ Detailed updates being shared with individual customers



Field Installation

- >75 units in the field across >9 end user customers
 - Various states of use across customer base
 - ie- qualification to pilot production
- No particle performance issues reported
- One trouble report associated with mechanics of outer pod
 - Currently under investigation
- Other tool suppliers have pods, Entegris supporting their development work as necessary
 - Metrology, Cleaning tool, Stocker suppliers

Shipping Status

- 3 options available
- New specification released targeting improved, reduced size secondary packaging for Type A shipping
 - Development efforts being reviewed



Shipping Option	Secondary Pkg Size	Test Status	Fully Automated Handling (once received)
Type A pod	1m x 1m x 1m palletized	G force testing complete, particle data not performed	Yes
Type B pod	20" x 20" x 18"	Many supporting data points, few outliers	With appropriate transfer tool
SMP625	17" x 17" x 17"	Limited testing shows acceptable performance	With appropriate transfer tool

Continued investment into EUV

■ Facilities

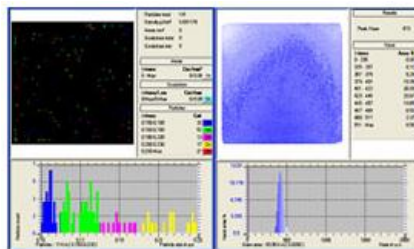
- Advanced Technology Manufacturing Center announced May 2011
 - 40k square foot facility to house Entegris' most advanced wafer and reticle handling manufacturing

■ Metrology

- <100nm mask blank level particle detection operational early Q1-12
- Used in R&D lab for performance and characterization testing

■ Market Leadership

- Standards
- Published papers



Defect Map of Mask Blank



Press Release for
Advanced Manufacturing
Center



Summary

- Manufacturing and Delivery of pods progressing
- Product allocation resolved by Jan 2012
- Deployment of pods at >9 customer sites. Pod performance data acceptable
- Shipping options exist
- Entegris continuing investment into EUV

